

Application No. 09/940,665  
Amendment dated December 11, 2003  
Reply to Office Action of June 17, 2003

**REMARKS**

Claims 1-25 are pending in this application, of which claims 1, 3-5, 12 and 13 have been amended. Claims 8-19, 21, 23 and 25 have been withdrawn from consideration. No new claims have been added.

**Specification**

The disclosure at lines 20-29 of page 3, lines 17-27 of page 9, lines 7-17 of page 11, lines 11-20 of page 14, and lines 1-10 of page 17 was objected to. The Office Action, paragraph 3. The structures of the chemical formulas are corrected in this Amendment. In addition, Applicants have corrected claims 12 and 13.

The disclosure at page 14, line 7 was objected to due to a typographical error. The Office Action, paragraph 4. Applicants have corrected the error in this Amendment.

**Claim Objections**

Claims 3-5 were objected to. The Office Action, paragraph 10. Applicants have corrected claim 3 to add a period at the end, and corrected typographical errors in claims 4 and 5.

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## **Claim Rejections – 35USC§102**

Claims 1, 2 and 4-5 were rejected under 35USC§102(e) as being anticipated by Kinsho et al. (US Patent 6,312,867).

Applicants traverse the rejections because Kinsho et al. do not disclose “a monomer compound having the combination of an acetal moiety and a site which is eliminated by an acid in its molecule.”

In Kinsho et al. a monomer having an acetal moiety is copolymerized with a monomer having a side which is eliminated by an acid, so as to obtain the polymer. Therefore, the acetal moiety and the site to be eliminated by an acid are located at different units in the polymer.

On the other hand, the chemically amplified resist composition of the present invention uses a monomer compound in which both the acetal moiety and the site (which is eliminated by an acid) are included. Therefore, the acetal moiety and the substituent on the site of carboxylate ester in the monomer compound cause elimination reactions, and the resultant hydroxyl and carboxyl groups easily react to produce the compound with a ring structure. Thus, the chemically amplified resist composition of the present invention has a very high reactivity, as described from page 6, line 10 to page 7, line 28. On the other hand, the polymer of Kinsho et al. will not generate a reaction between the acetal moiety and the acid-eliminated site, since they are located at different units each

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other. Reconsideration of the rejections is respectfully requested.

### **Claim Rejections – 35USC§103**

Claims 6 and 7 were rejected under 35USC§103(a) as being unpatentable over Kinsho et al. (US Patent 6,312,867). Office Action, paragraph 14.

Since claims 6 and 7 depend on claim 1 whose rejection is traversed, the rejection of claims 6 and 7 is not supported. Reconsideration of the rejection is respectfully requested.

Claims 1, 2, 4-7, 20, 22 and 24 were rejected under 35USC§103(a) as being unpatentable over Nakanishi et al. (US Patent 6,537,726) in view of Kinsho et al. ((US Patent 6,312,867) and Grober et al. (US Patent 6,376,149). Office Action, paragraph 15.

The polymers disclosed by Nakanishi et al. and Grober et al. have the acetal moieties and the acid-eliminated sites, but both are located at different units of the polymers. Therefore, a reaction between the acetal moiety and the acid-eliminated site will not occur. Therefore, even if one combined Nakanishi et al. with Kinsho et al. and Grober et al., the present invention is not obtained. Reconsideration of the rejection is respectfully requested.

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In view of the aforementioned amendments and accompanying remarks, claims 1-7, 20, 22 and 24, as herein amended, are in condition for allowance. Applicants request such action at an early date.

If the Examiner believes that this application is not now in condition for allowance, the Examiner is requested to contact Applicants' undersigned attorney at the telephone number indicated below to arrange for an interview to expedite the disposition of this case.

In the event that this paper is not timely filed, Applicants respectfully petition for an appropriate extension of time. The fees for such an extension or any other fees that may be due with respect to this paper may be charged to Deposit Account No. 50-2866.

Respectfully submitted,

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